

Removal of Photoresist Residue using Supercritical Carbon Dioxide

장원호, 임종성, 한갑수, 유기풍*, 원종우
서강대학교
(kpyoo@sogang.ac.kr*)

Supercritical CO₂-based fluid is not only being considered as environmentally benign medium for various field as alternative solvent, but also capable of challenging feature dimensions. Despite many attractive properties such as highly integrated electronic device, pure supercritical CO₂ has little solvating power for polar components. In this work, fluorinated surfactants and modifiers were added to increase solvating power of supercritical CO₂ for photo-resist. Removing residue of photo-resist called rabbit ear was investigated. Metal patterned and PR coated wafer is employed as cleaning target. Temperature, pressure and amount of additive were varied to optimize process.